



RF Plasma Multifunction Reactor

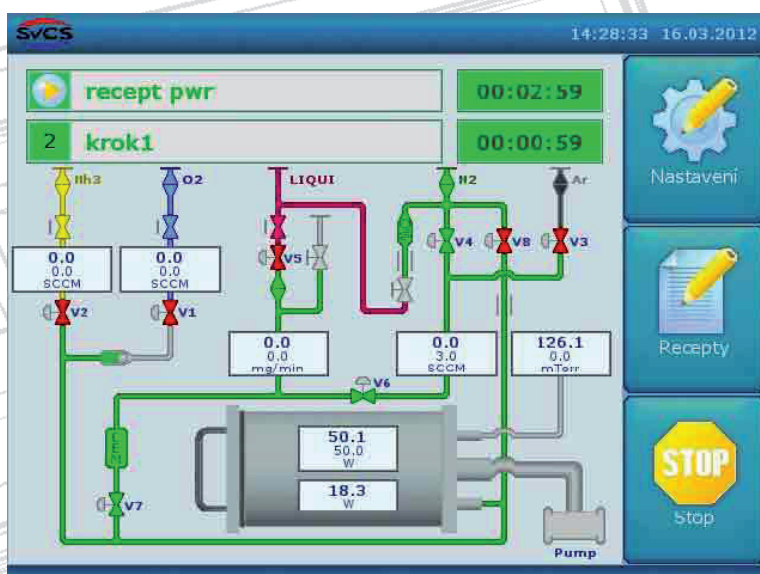
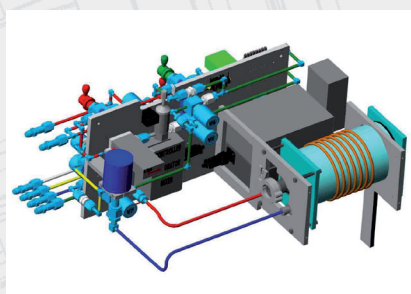
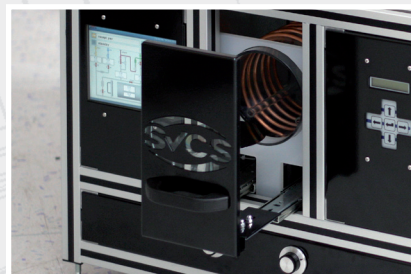
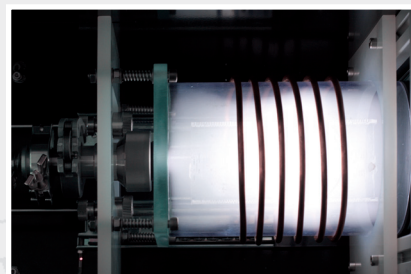
Versatile tool for dedicated demanding research

INTRO

SVCS plasma reactor system is fully automatic compact table top equipment, custom designed and built for particular research needs. It can be used for broad range of R&D applications including (but not limited to) well known processes as deposition, etching, ashing.

FEATURES

Process media dosing, vacuum and temperature control are independent on each other which provides high degree of process flexibility. Process media selection is broad. Not only gaseous but also liquid/vapour reagents are possible with precise electronic dosing amount control and high performance evaporator. The ultra high purity system design, with electronic mass flow control for both gases and liquids, allows to use also corrosive, flammable or toxic media with no safety risk for research personnel. Plasma RF generators are available with a range of frequencies and power levels, associated tuning circuits for both capacitively and inductively coupled plasma. Chamber pressure is controlled by butterfly control valve or gas ballast system. Control system with touch screen interface allows user to create process recipes with unlimited possibilities to set all process variables.





SVCS Process Innovation s.r.o.
 Optátova 37, 637 00 Brno
 CZECH REPUBLIC
 e-mail: info@svcs.eu
 http://www.svcs.eu



SVCS CO.
 330 S Pineapple Ave. S-110
 Sarasota, Florida 34236, USA
 e-mail: info@svcsapi.com
 http://www.svcsapi.com



ООО „SVCS“
 Солнечная аллея дом 6 • офис 223
 124498 Москва • Зеленоград • РОССИЯ
 e-mail: info@svcs.ru
 http://www.svcs.ru

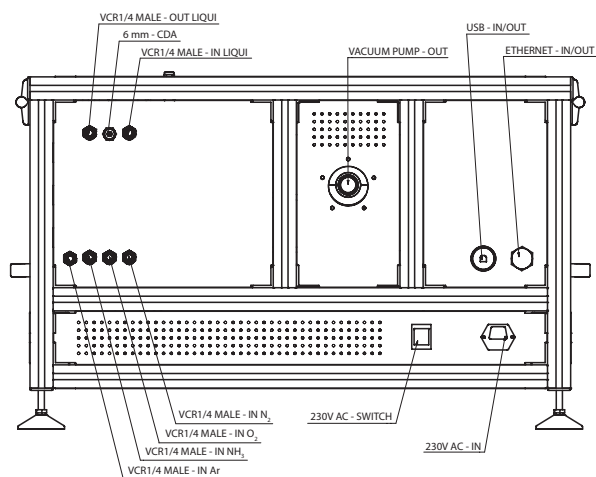
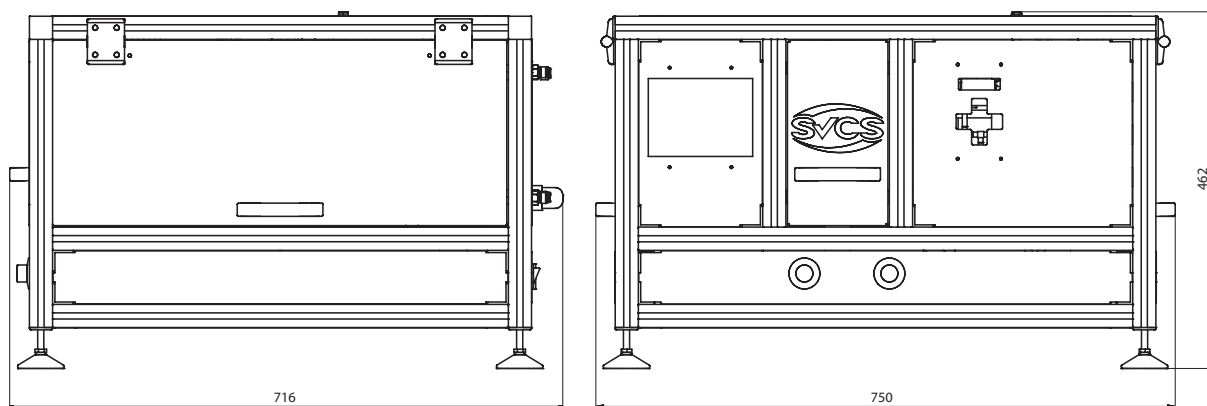


RF Plasma Multifunction Reactor

Technical Data

Chamber size	cylindrical, 110 mm diameter, 180 mm length
Temperature range	ambient (optionally heated up to 350 °C)
Pressure range	vacuum to atmospheric pressure
Process media	up to 5 ultra-high purity gas lines with electronic mass flow control 1 liquid reagent with evaporator and precise mass dosing
RF frequencies	13,56 MHz, optionally 40 and 450 kHz
RF power	100 W
Option	additional gas and liquid lines in a custom designed enclosure vacuum pumping system

DIMENSIONS



*Dimensions are varying with configuration,
 please consult factory.*



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